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TO: Assistant Commissioner for Patents
Washington, D.C. 20231

FAX NO.: 703-308-7382

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KINDLY DIRECT THIS COMMUNICATION TO:

EXAMINER : M. Whipple
GROUP : 2813

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

HUI-JUNG WU, ET AL ✓

Docket : 30-4510 (1780)

Serial Number: 09/141,287 ✓

Group Art Unit: 2813

Filed: August 27, 1998 ✓

Examiner: M. Whipple

For: PROCESS FOR OPTIMIZING MECHANICAL STRENGTH
OF NANOPOROUS SILICA ✓AMENDMENT7/A
9-24-99
J ProctorAssistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Office Action mailed June 22, 1999, please amend the above identified patent application as follows:

In the claims:

1. A process for forming a nanoporous dielectric coating on a substrate which comprises:

(a) forming a substantially uniform alkoxysilane gel composition on a surface of a substrate, which alkoxysilane gel composition comprises a combination of at least one alkoxysilane, an organic solvent composition, water, and an optional base catalyst;

wherein the organic solvent composition comprises a relatively high volatility solvent having a boiling point of about 120 °C or less, and a relatively low volatility solvent

selected from the group consisting of di(ethylene)glycol monomethyl ether,

tri(ethylene)glycol monomethyl ether, tetra(ethylene)glycol monomethyl ether;

di(propylene)glycol monomethyl ether, tri(propylene)glycol monomethyl ether, triethylene glycol monomethyl ether, and mixtures thereof;

(b) heating the substrate for a sufficient time and at a sufficient temperature in an organic solvent vapor atmosphere to thereby condense the gel composition; and then

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